



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re Patent Application of

YAMAMURA *et al.*

Appln. No.: 09/924,116

Group Art Unit: tbd

Filed: August 8, 2001

Examiner: tbd

For: PHOTOCURABLE LIQUID RESIN COMPOSITION

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April 19, 2002

SUPPLEMENTAL PRELIMINARY AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

Prior to examination on the merits, please amend the application in the manner set forth below.

IN THE CLAIMS

Please enter new claims 33-42.

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TC 1700

- Sub D1
- C1
33. (New) A photocurable resin composition comprising:
- (A) an epoxy compound having two or more alicyclic epoxy groups;
 - (B) a cationic photopolymerization initiator;
 - (C) dipentaerythritol penta(meth)acrylate;
 - (D) a radical photopolymerization initiator; and
 - (E) a polyol having three or more hydroxyl groups in one molecule.

34. (New) The composition of claim 33, wherein said polyol is a polyether polyol.